

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-10. (Canceled)

11. (Previously Presented) A plasma generator comprising:

a) a vacuum chamber;

b) a stage located within the vacuum chamber, on which a base plate is to be placed; and

c) three or more RF antennas provided on an inner wall surface of the vacuum chamber

so as to surround an inner place of the vacuum chamber, adjacent electrodes of one or more pairs of adjacent RF antennas having the same polarity,

wherein the three or more RF antennas are substantially U-shaped, and

wherein one electrode of each RF antenna is connected to a power source and an other electrode of each RF antenna is connected to a ground.

12. (Previously Presented) The plasma generator according to claim 11, wherein the adjacent electrodes of every pair of the adjacent RF antennas have the same polarity.

13.-31. (Canceled)

32. (Currently Amended) A plasma control method using a plasma generator having three or more RF antennas located within a vacuum chamber, said antennas being arranged on one or both of a sidewall and a ceiling wall of the vacuum chamber so as to surround an inner space of the vacuum chamber, wherein a plasma density distribution within the plasma generator is controlled by giving ~~an equal~~ a same polarity to adjacent electrodes of one or more pairs of adjacent RF antennas,

wherein the three or more RF antennas are substantially U-shaped, and

wherein one electrode of each RF antenna is connected to a power source and an other electrode of each RF antenna is connected to a ground.

33. (Previously Presented) The plasma control method according to claim 32, wherein the adjacent electrodes of every pair of the adjacent RF antennas have the same polarity.

34.-39. (Canceled)

40. (Previously Presented) The plasma generator according to claim 11, wherein the RF antennas are attached on one or both of a sidewall and a ceiling wall of the vacuum chamber.

41.-42. (Canceled)

43. (Previously Presented) The plasma generator according to claim 11, wherein a surface of the RF antennas is coated with an insulator.

44.-45. (Canceled)

46. (Previously Presented) The plasma generator according to claim 11, wherein the shape of the RF antennas within the vacuum chamber is flat.

47.-48. (Canceled)

49. (Previously Presented) The plasma generator according to claim 11, wherein each of the multiple RF antennas are divided into groups each including one or more RF antennas, and a RF power is supplied to each RF antenna in parallel within each group.

50.-51. (Canceled)

52. (Previously Presented) A method of producing a substrate, wherein plasma of a material is generated by a plasma generator according to claim 11 and the material is deposited.

53.-54. (Canceled)

55. (Previously Presented) A method of producing a substrate, wherein an etching process is carried out using plasma generated by a plasma generator according to claim 11.

56. (Canceled)